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(12) **United States Design Patent**
Lee

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(54) **MASK**

(76) **Inventor:** **Chi Keung Lee**, Unit B, 22/F.,
Richwealth Industrial Building, 77-87
Wang Lung Street, Tsuen Wan, New
Territories, Hong Kong (CN)

(**) **Term:** **14 Years**

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(51) **LOC (8) Cl.** **29-02**

(52) **U.S. Cl.** **D29/108**

(58) **Field of Classification Search** D29/102-111,
D29/122; 2/9, 6.3, 6.7, 15, 10, 452, 410,
2/422-425, 427, 431, 436, 206; 128/207.11,
128/857-858, 201.17, 201.19, 201.23, 201.24,
128/206.21, 206.12, 206.28; D24/110.2,
D24/110.3; D16/300, 301, 309, 310, 312
See application file for complete search history.

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Primary Examiner—Ruth McInroy

(74) *Attorney, Agent, or Firm*—Alix, Yale & Ristas, LLP

(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a front perspective view of a mask showing my new design;

FIG. 2 is a front view thereof;

FIG. 3 is a rear view thereof;

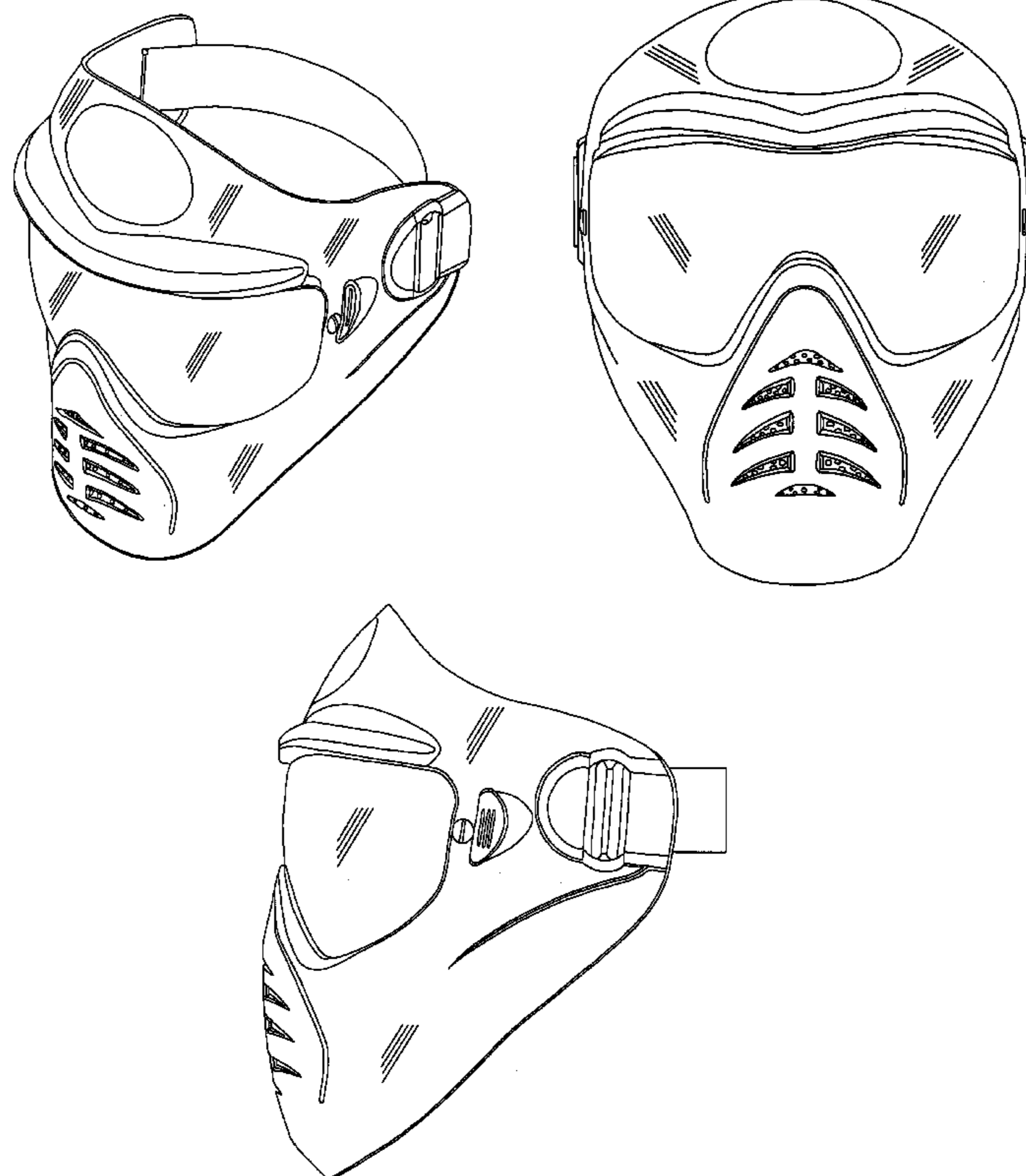
FIG. 4 is a left side view thereof;

FIG. 5 is a right side view thereof;

FIG. 6 is a top plan view thereof; and,

FIG. 7 is a bottom plan view thereof.

1 Claim, 7 Drawing Sheets



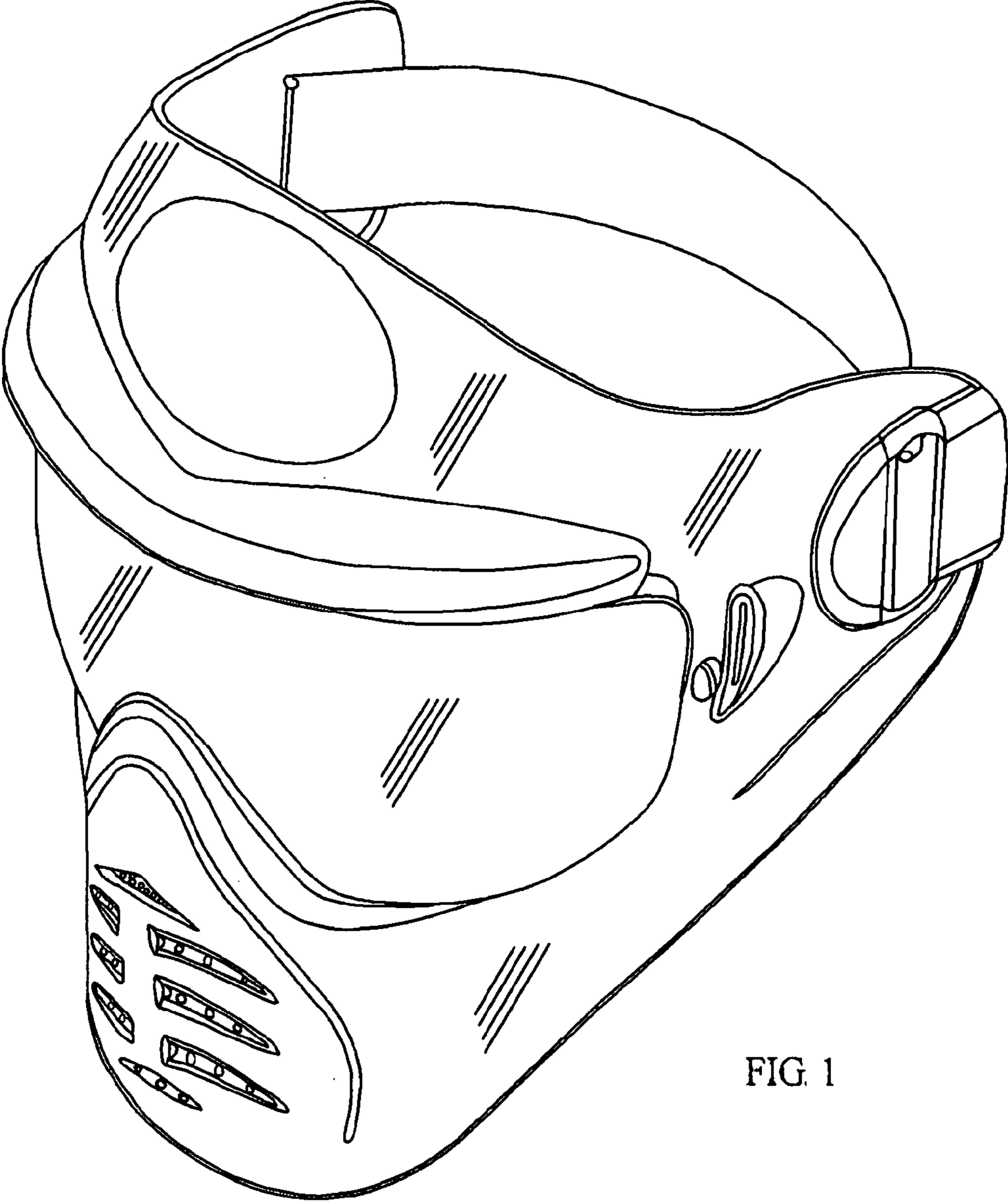


FIG. 1



FIG. 2

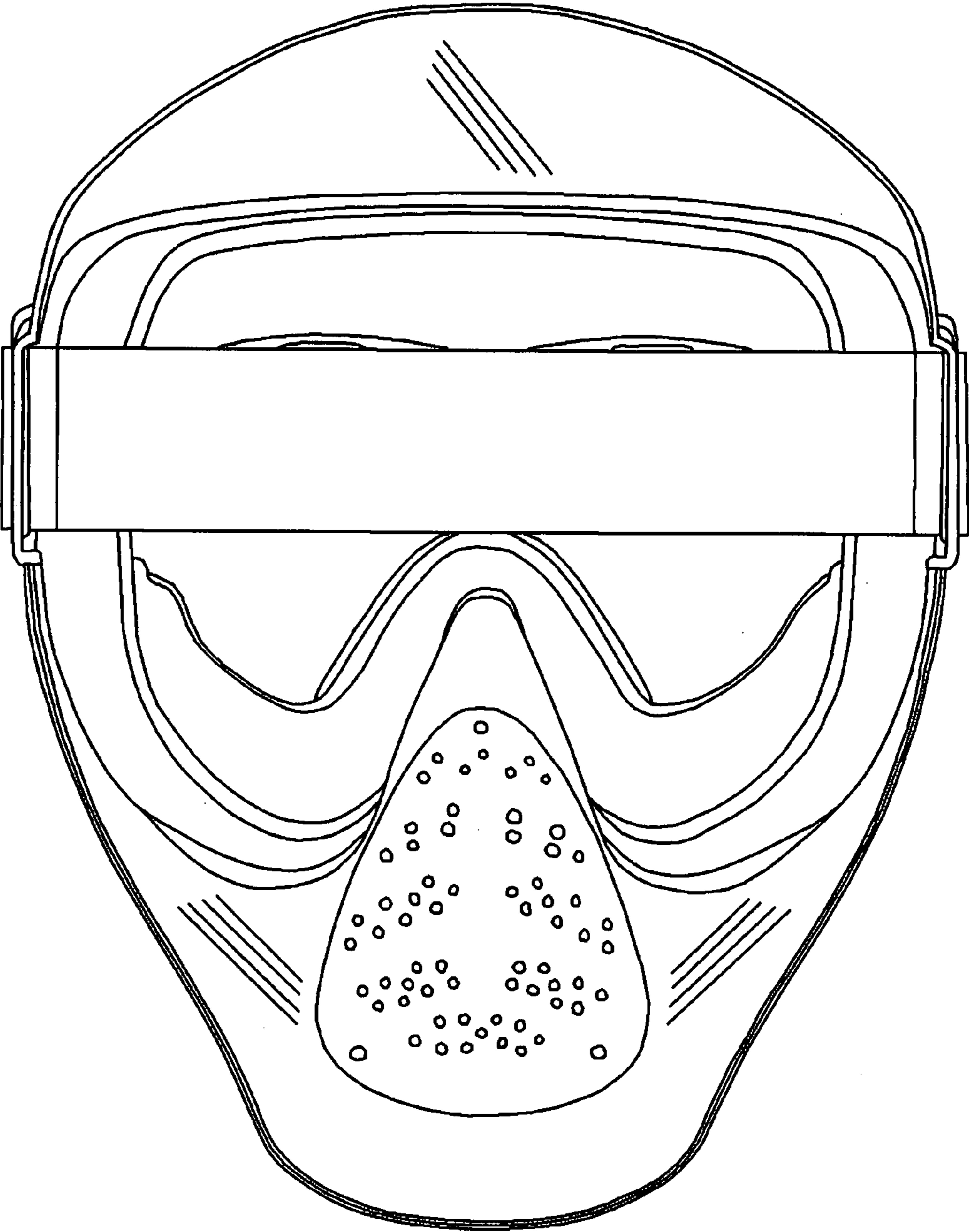


FIG. 3

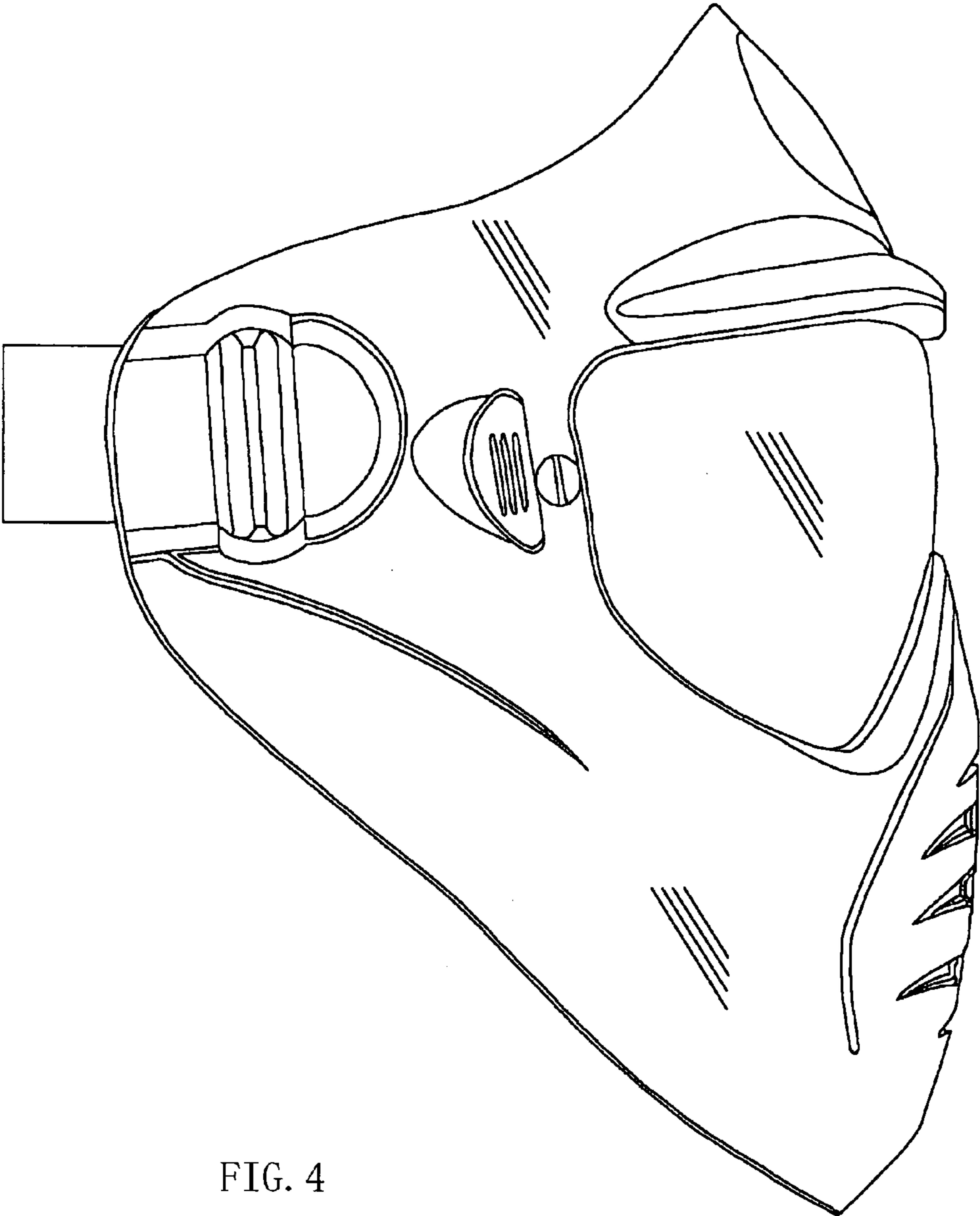


FIG. 4

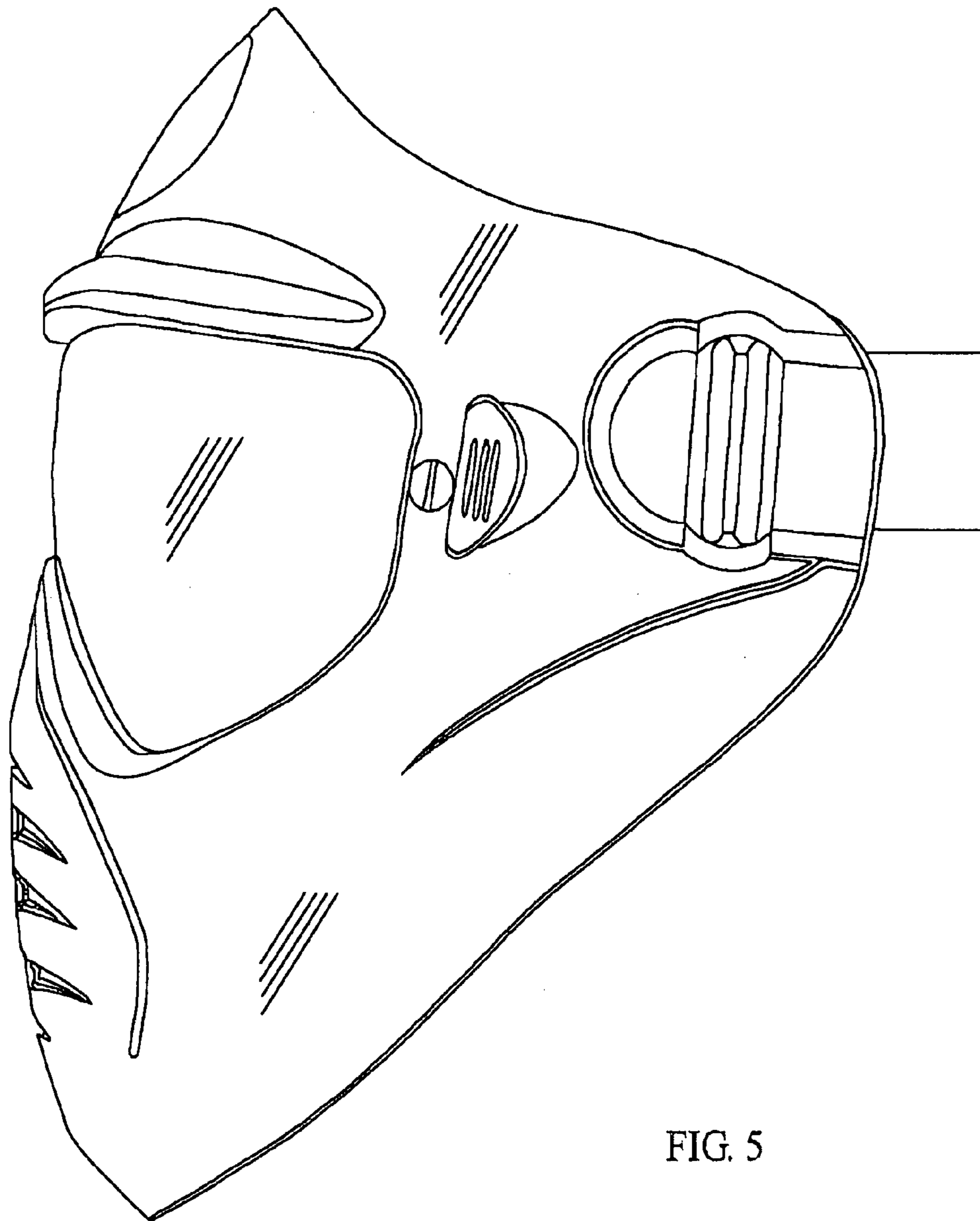


FIG. 5

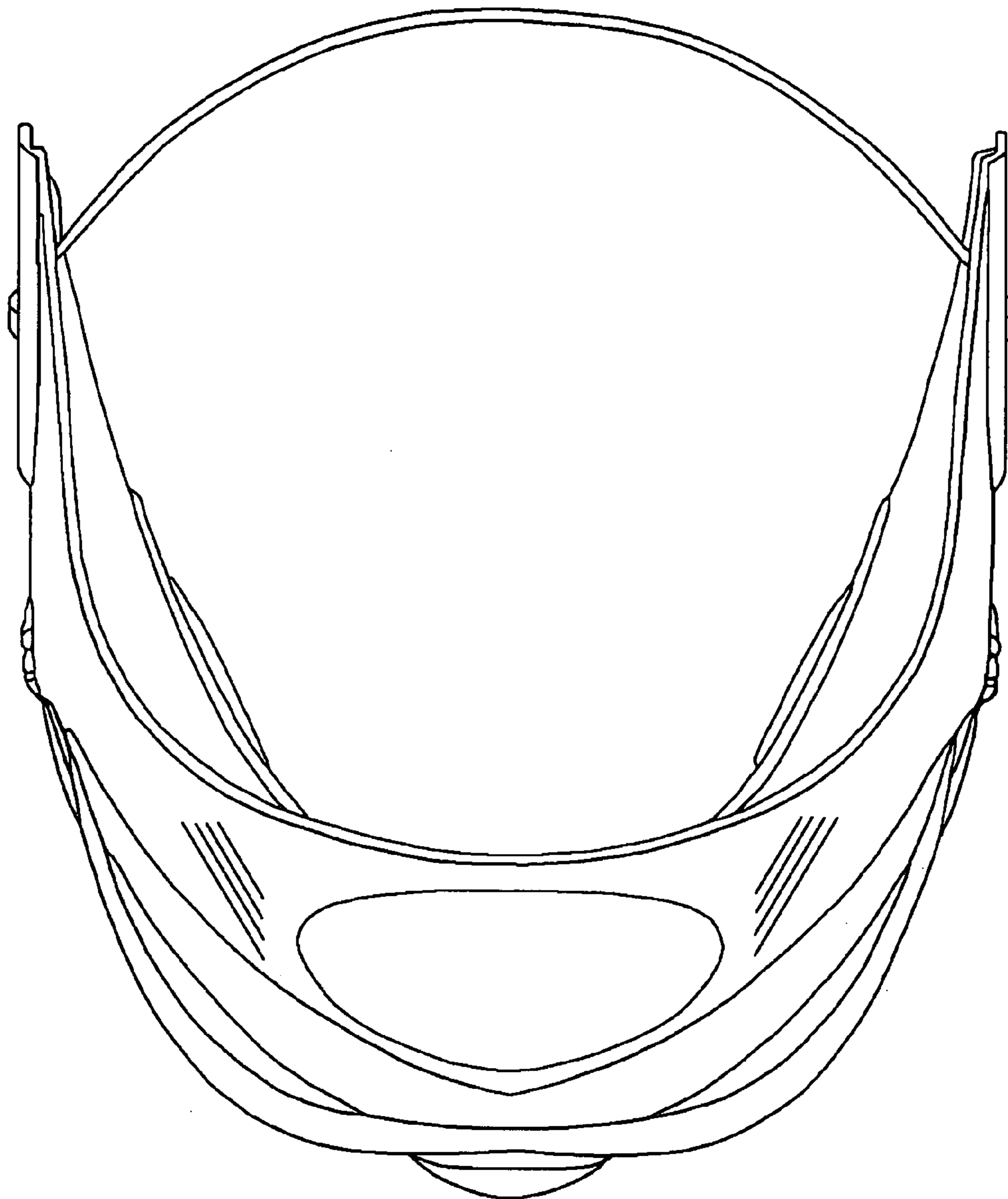


FIG. 6

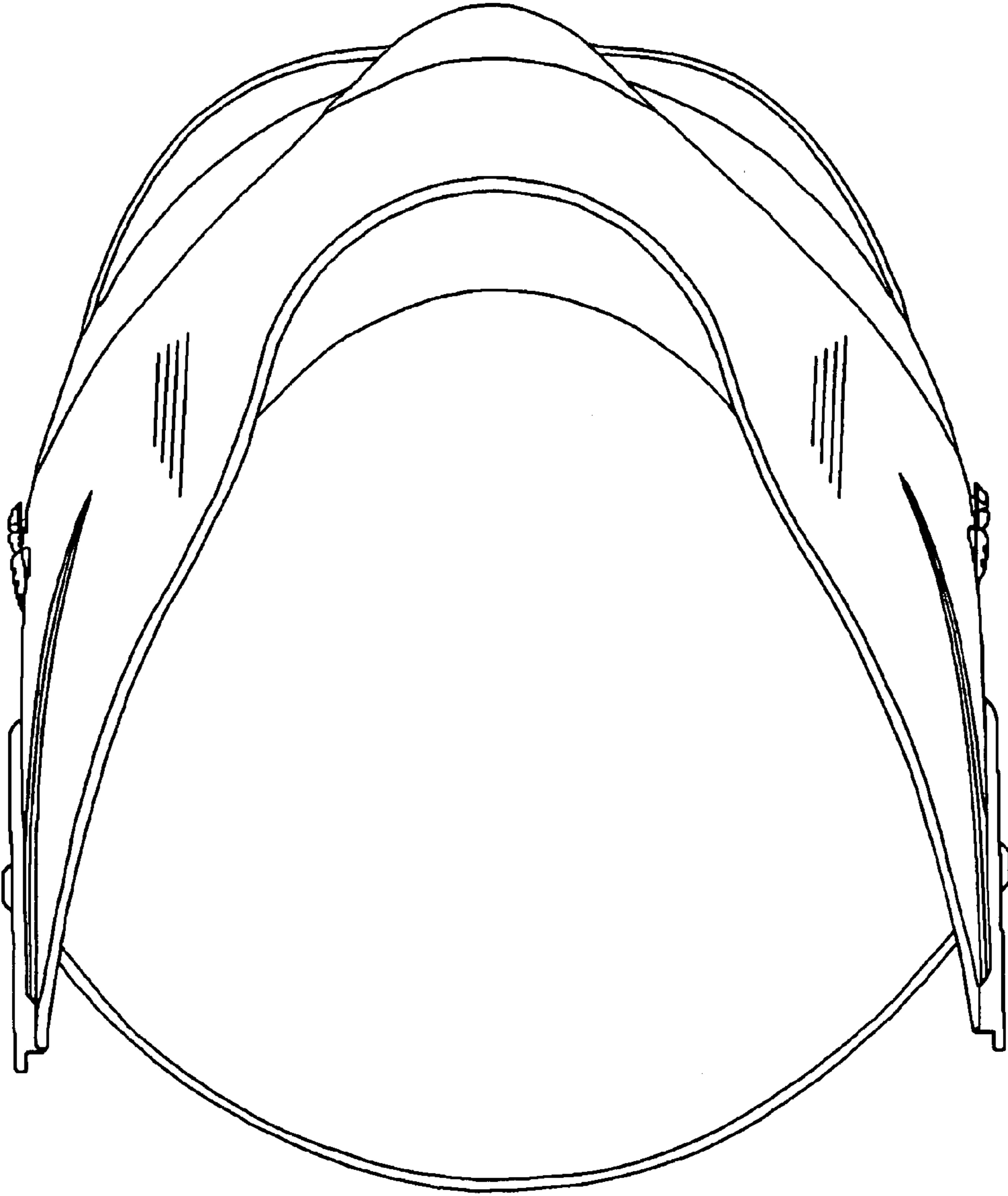


FIG. 7